

Application No. 10/021,012

Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A liquid crystal panel substrate, comprising:
reflecting electrodes formed on a substrate;
a switching element formed corresponding to each of the reflecting electrodes;
a passivation film formed on said reflecting electrodes comprising a silicon oxide film; and
a silicon nitride film formed as an insulating interlayer between said reflecting electrodes and a metal shielding layer above the switching element thereunder ~~having moisture resistance,~~ wherein the metal layer shields incident light for preventing pixel switching.
2. (Original) A liquid crystal panel substrate according to claim 1, wherein said insulating interlayer between said reflecting electrodes and said metal layer thereunder comprises a silicon nitride film and a silicon oxide film, and has a laminate structure in which said silicon nitride film is formed on said silicon oxide film.
3. (Currently Amended) A liquid crystal panel substrate comprising:
a pixel region having a matrix of reflecting electrodes formed on a substrate and a switching element formed corresponding to each of said reflecting electrodes, a periphery region of said pixel region on the substrate having at least insulating interlayers; and
a passivation film having a laminate structure comprising a silicon oxide film and a silicon nitride film on said silicon oxide film, the passivation film being formed at least on a thickness side of ~~edge sections of the~~ at least insulating interlayers.

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4. (Currently Amended) A liquid crystal panel substrate comprising:

- a pixel region having a matrix of reflecting electrodes formed on a substrate and a transistor formed corresponding to each of the reflecting electrodes;
- a peripheral circuit arranged in a periphery region of said pixel region on the substrate for supplying signals to said transistors in said pixel region;
- a first passivation film comprising a silicon oxide film formed on said reflecting electrodes in said pixel region; and
- a second passivation film comprising a silicon nitride film formed at least on a thickness side of edge sections of said periphery region.

5. (Original) A liquid crystal panel substrate according to claim 4, the silicon nitride film being a first silicon nitride film, the liquid crystal panel substrate further comprising a second silicon nitride film as an insulating interlayer provided between said reflecting electrodes and a metal layer thereunder.

6. (Original) A liquid crystal panel substrate according to claim 5, the silicon oxide film being a first silicon oxide film, said insulating interlayer between said reflecting electrodes and said metal layer thereunder comprising the second silicon nitride film and a second silicon oxide film, and having a laminate structure in which said second silicon nitride film is formed on said second silicon oxide film.

7. (Original) A liquid crystal panel substrate comprising:

- a pixel region having a matrix of reflecting electrodes formed on a substrate and transistor formed corresponding to each of the reflecting electrodes;
- a peripheral circuit arranged in a periphery region of said pixel region on the substrate for supplying signals to said transistors in said pixel region, the periphery region having a metal layer and an insulating layer;

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a first passivation film comprising a first silicon oxide film formed in said pixel region; and

a second passivation film having a laminate structure comprising a second silicon oxide film and a silicon nitride film formed on the second silicon oxide film, the second passivation film being formed at edge sections of the metal layer and the insulating interlayer.

8. (Original) A liquid crystal panel substrate according to claim 3, further comprising a seal material formed on said silicon nitride film for sealing with a counter substrate.

9. (Previously Presented) A liquid crystal panel substrate according to claim 3, said edge section of said insulating interlayers being a scribed region of the substrate.

10. (Currently Amended) A liquid crystal panel substrate comprising:
a pixel region having reflecting electrodes formed on a semiconductor substrate and a switching element formed corresponding to each of the reflecting electrodes;
a scribed region formed on the periphery of the pixel region; and
a passivation film formed by a silicon nitride film ~~having moisture resistance~~ and formed on ~~the~~ scribed region of said semiconductor substrate.

11. (Original) A liquid crystal panel substrate according to claim 10, said passivation film having a laminate structure comprising a silicon oxide film and the silicon nitride film formed on the silicon oxide film.

12. (Currently Amended) A liquid crystal panel, comprising:
a first substrate;
a second substrate opposed to the first substrate;
a liquid crystal therebetween, and
a seal material sealing the first substrate and the second substrate;

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a pixel region having reflecting electrodes formed on said first substrate; and
a passivation film comprising a silicon nitride film formed in a region
arranged with said seal material on said first substrate, the seal material being formed on the
silicon nitride, ~~and the passivation film extending on a scribed region of the first substrate.~~

13. (Original) A liquid crystal panel according to claim 12, the passivation film
being a first passivation film and the liquid crystal panel further comprising a second
passivation film comprising a silicon oxide film formed on the reflecting electrodes.

14. (Currently Amended) A liquid crystal panel substrate, comprising:
reflecting electrodes formed on a substrate;
a switching element formed corresponding to each of the reflecting electrodes;
a passivation film formed on the reflecting electrodes comprising a silicon
oxide film; and

a light shielding layer disposed under the reflective electrodes and a space
between adjacent reflecting electrodes so as to cover the switching element; and

a silicon nitride film formed as an insulating interlayer between the reflecting
electrodes and the switching element ~~light shielding layer so as to cover the switching element~~
except for a connection portion between the reflecting ~~electrode~~ electrodes and the switching
element.

15. (Previously Presented) The liquid crystal substrate according to claim 7, the
second silicon oxide layer being the same layer as the first silicon oxide layer.